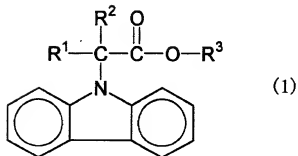


ABSTRACT OF THE DISCLOSURE

A carbazole derivative of the following formula (1),



wherein R^1 and R^2 individually represent a hydrogen atom or a monovalent organic group, or R^1 and R^2 form, together with the carbon atom to which R^1 and R^2 bond, a divalent organic group having a 3-8 member carbocyclic structure or a 3-8 member heterocyclic structure, and R^3 represents a hydrogen atom or a monovalent organic group. The carbazole derivative is suitable as an additive for increasing sensitivity of a chemically amplified resist. A chemically amplified radiation-sensitive resin composition, useful as a chemically amplified resist, comprising the carbazole derivative is also disclosed.